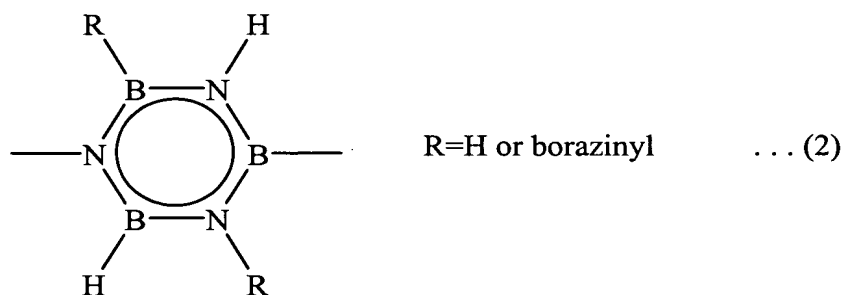
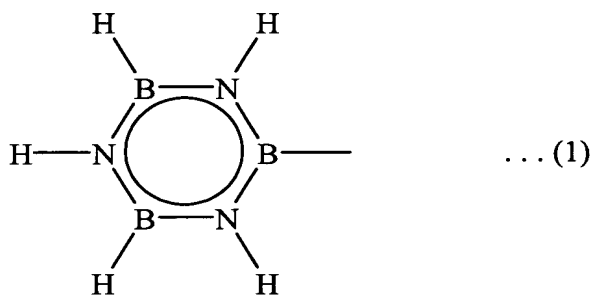


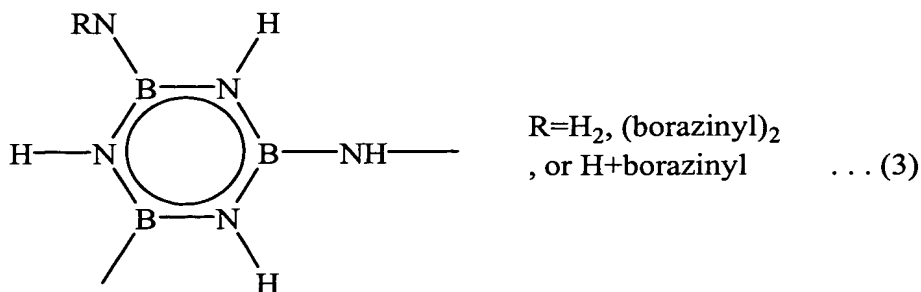
REMARKS

Applicants thank the Examiner for the courtesy extended to Applicants' attorney during the interview held March 23, 2004, in the above-identified application. During the interview, Applicants' attorney explained the presently-claimed invention and why it is patentable over the applied prior art, and discussed other issues raised in the Office action. The discussion is summarized and expanded upon below.

The rejection of Claims 1-3 under 35 U.S.C. § 103(a) as unpatentable over U.S. 5,188,757 (Paine et al), is respectfully traversed.

The present invention is based on Applicants' discovery that inorganic or organic compounds having a particular borazine skeletal moiety therein can result in materials having a relatively low dielectric constant and relatively high thermal resistance. The moieties may have one of the following formulae (1), (2), or (3):





As recited in above-amended Claim 1, the claimed invention is an insulation film between semiconductor layers comprising the above-discussed material. As described in the specification at page 16, lines 7-10, since electronic signal retardation becomes small by applying the insulation film to a semiconductor device such as a IC substrate or electric appliances, high speed of the device can be achieved.

Paine et al is drawn to precursor compositions for conversion to boron nitride. Particularly, Paine et al discloses polymeric B-aminoborazine compounds for pyrolytic conversion to boron nitride. However, Paine et al neither discloses nor suggests any of their precursor compounds for anything other than as intermediates for the production of boron nitride *per se*. Nor is there any reason to expect that Paine et al's intermediates meet the dielectric constant and thermal resistance limitations of the present claims. In other words, Paine et al neither discloses nor suggests the presently-claimed subject matter. In addition, Paine et al's disclosure about excellent dielectric and other properties (column 1, lines 31-35) is in reference to **boron nitride**, not the above-discussed precursor compounds.

For all the above reasons, it is respectfully requested that the rejection over Paine et al be withdrawn.

The rejection of Claims 1-3 under the judicially created doctrine of obviousness-type double patenting over Claims 1, 6 and 8 of U.S. 6,458,719 (Tsunoda et al), is respectfully traversed. **Submitted herewith** is a Terminal Disclaimer over Tsunoda et al. Accordingly, it is respectfully requested that the rejection be withdrawn.

The rejection of Claims 2 and 3 under 35 U.S.C. § 112, second paragraph, is respectfully traversed. Indeed, the rejection is now moot in view of the above-discussed amendment. Accordingly, it is respectfully requested that it be withdrawn.

The objection to Claim 2 is respectfully traversed. Indeed, the objection is now moot in view of the above-discussed amendment. Accordingly, it is respectfully requested that it be withdrawn.

Applicants respectfully call the Examiner's attention to the Information Disclosure Statement (IDS) filed August 31, 2001. The Examiner is respectfully requested to initial the Form PTO 1449 submitted therewith, and include a copy thereof with the next Office communication. For the Examiner's convenience, another copy of the Form is **submitted herewith**.

Moreover, since the date of the IDS is before the date of the Office Action and thus technically was part of the Official file as of the Office Action date, Applicants respectfully request that should the Examiner determine that a new ground of rejection needs to be made in the next Office Action relying in whole or in part on any of the references cited in the IDS, then said next Office Action not be made Final, even if the new rejection was necessitated by the present amendment to the claims.

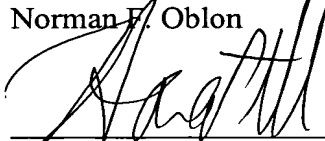
Application No. 09/942,626
Reply to Office Action of March 1, 2004

All of the presently pending claims in this application are now believed to be in immediate condition for allowance. Accordingly, the Examiner is respectfully requested to pass this application to issue.

Respectfully submitted,

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